

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	14	("6258649" "6255151" "6261883" "6027983" "5539240" "6143626" "6337282" "5098856" "6133105" "6060352" "6483136" "6111086" "0182798" "6121086").PN.	US-PGPUB; USPAT	OR	OFF	2005/07/09 19:09
S2	4	"5827782".pn. "5960300".pn. "20020182798".pn. "6693008".pn.	US-PGPUB; USPAT	OR	OFF	2005/07/06 13:04
S3	8	jp-11145286-\$ did. jp-05235157-\$ did. jp-05114046-\$ did. ep-851463-\$ did. kr-9404776-\$ did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/07/09 17:04
S4	3	jp-05114646-\$ did. 1994kr-0004776.ap,prai.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/07/11 13:28
S5	1	"20010022369".pn.	US-PGPUB; USPAT	OR	OFF	2005/07/09 17:55
S6	5589	257/510.ccls. 257/622.ccls. 257/635.ccls. 438/296.ccls. 438/424.ccls. 438/435.ccls. 438/763.ccls. 438/781.ccls. 438/782.ccls. 438/926.ccls.	US-PGPUB; USPAT	OR	OFF	2005/07/09 19:13
S7	2839	S6 and ((trench groove opening) same (gate dummy pattern\$6) same (dielectric insulat\$6 oxide dioxide nitride))	US-PGPUB; USPAT	OR	ON	2005/07/11 13:31
S8	734	S6 and ((trench groove opening) same ((gate dummy) with (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8)) same (dielectric insulat\$6 oxide dioxide nitride))	US-PGPUB; USPAT	OR	ON	2005/07/09 19:21
S9	627	S6 and (((trench groove opening) with (dielectric insulat\$6 oxide dioxide nitride)) same ((gate dummy) with (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8)))	US-PGPUB; USPAT	OR	ON	2005/07/09 19:19
S11	7477	(trench groove opening) and (gate dummy) and (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8) and (dielectric insulat\$6 oxide dioxide nitride)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/11 13:38
S12	2673	(trench groove) and (gate dummy) and (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8) and (dielectric insulat\$6)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 19:22

S13	1635	(trench groove) same (gate dummy) same (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8) same (dielectric insulat\$6)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 19:23
S14	403	(trench groove) same ((gate dummy) near2 (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8)) same (dielectric insulat\$6)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/09 19:23
S15	274	(trench groove) same ((gate dummy) near2 pattern\$6) same (dielectric insulat\$6)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/12 15:47
S16	841	(trench groove) with ((gate dummy) near2 (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8)) with (dielectric insulat\$6 oxide dioxide nitride)	US-PGPUB; USPAT	OR	ON	2005/07/11 13:41
S17	593	(trench groove) with ((gate dummy) near2 (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8)) with (dielectric insulat\$6)	US-PGPUB; USPAT	OR	ON	2005/07/09 19:26
S18	393	(trench groove) with ((gate dummy) near2 pattern\$6) with (dielectric insulat\$6)	US-PGPUB; USPAT	OR	ON	2005/07/12 16:42
S19	5589	257/510.ccls. 257/622.ccls. 257/635.ccls. 438/296.ccls. 438/424.ccls. 438/435.ccls. 438/763.ccls. 438/781.ccls. 438/782.ccls. 438/926.ccls.	US-PGPUB; USPAT	OR	OFF	2005/07/11 13:37
S22	257	(trench groove opening) and (gate dummy pattern\$6 mask\$6 lithograph\$8 photolithograph\$8) and (dielectric insulat\$6 oxide dioxide nitride) and (sog "spin-on glass" "spin on glass" (sp?non adj glass) polysilazane)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/11 13:39
S23	28	(trench groove) same ((gate dummy) near4 (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8)) same (dielectric insulat\$6 oxide dioxide nitride) same (sog "spin-on glass" "spin on glass" (sp?non adj glass) polysilazane)	US-PGPUB; USPAT	OR	ON	2005/07/11 13:42
S25	2	jp-08125008-.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/07/11 13:43
S26	5589	257/510.ccls. 257/622.ccls. 257/635.ccls. 438/296.ccls. 438/424.ccls. 438/435.ccls. 438/763.ccls. 438/781.ccls. 438/782.ccls. 438/926.ccls.	US-PGPUB; USPAT	OR	OFF	2005/07/11 14:33

S27	330	S26 and (((trench groove) with (dielectric insulat\$6)) same ((gate dummy) with (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8)))	US-PGPUB; USPAT	OR	ON	2005/07/11 14:33
S28	274	(trench groove) same ((gate dummy) near2 pattern\$6) same (dielectric insulat\$6)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/12 15:47
S29	394	(trench groove) with ((gate dummy) near2 pattern\$6) with (dielectric insulat\$6)	US-PGPUB; USPAT	OR	ON	2005/07/14 14:32
S30	5595	257/510.ccls. 257/622.ccls. 257/635.ccls. 438/296.ccls. 438/424.ccls. 438/435.ccls. 438/763.ccls. 438/781.ccls. 438/782.ccls. 438/926.ccls.	US-PGPUB; USPAT	OR	OFF	2005/07/13 14:50
S31	83	S30 and ((trench groove opening) same (gate dummy pattern\$6) same (dielectric insulat\$6 oxide dioxide nitride) same (sog "spin-on glass" "spin on glass" (sp?non adj glass) polysilazane))	US-PGPUB; USPAT	OR	ON	2005/07/13 14:50
S32	14	("20020004282" "4222792" "4671970" "5382541" "5387539" "5435888" "5445989" "5492858" "5504033" "6030881" "6057209" "6300219" "6316331").PN. OR ("6756654").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/07/14 11:09
S33	16	("20020055271" "20020063334" "20020072198" "20020072246" "20020127817" "20020168873" "6194283" "6232216" "6294833" "6489252").PN. OR ("6566229").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/07/13 15:48
S34	41	(trench groove opening) and (gate dummy) and (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8) and (dielectric insulat\$6 oxide dioxide nitride) and (sog "spin-on glass" "spin on glass" (sp?non adj glass) polysilazane)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/13 16:01
S35	51	(trench groove) same ((gate dummy) with (pattern\$6 mask\$6 lithograph\$8 photolithograph\$8)) same (dielectric insulat\$6 oxide dioxide nitride) same (sog "spin-on glass" "spin on glass" (sp?non adj glass) polysilazane)	US-PGPUB; USPAT	OR	ON	2005/07/13 16:15

S36	38	("3990927" "4474975" "5156881" "5182221" "5410176" "5470798" "5719085" "5741740" "5776557" "5786039" "5801083" "5863827" "5888880" "5895253" "5904540" "5930645" "5943585" "5950094" "5960299" "5972773" "5998280" "6030881" "6051477" "6156674").PN. OR ("6300219").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/07/14 11:10
S37	25	(gate with dummy) same (gap near2 fill\$6)	US-PGPUB; USPAT	OR	ON	2005/07/14 16:33
S38	8	(gate with dummy) and (gap near2 fill\$6)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/14 16:33
S39	458	(gate dummy) and (gap near2 fill\$6)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/14 16:33
S40	801	(gate dummy) with (gap near2 fill\$6)	US-PGPUB; USPAT	OR	ON	2005/07/14 16:34
S41	20	S40 same (cvd (chemical adj vapor)) same (sog "spin-on glass" "spin on glass" (sp?non adj glass) polysilazane)	US-PGPUB; USPAT	OR	ON	2005/07/14 16:42
S42	1	S39 and (cvd (chemical adj vapor)) and (sog "spin-on glass" "spin on glass" (sp?non adj glass) polysilazane)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/14 16:44
S43	34	S39 and (cvd (chemical adj vapor) sog "spin-on glass" "spin on glass" (sp?non adj glass) polysilazane)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/14 17:00
S44	175	S40 same (cvd (chemical adj vapor) sog "spin-on glass" "spin on glass" (sp?non adj glass) polysilazane)	US-PGPUB; USPAT	OR	ON	2005/07/14 17:00
S45	65	S40 with (cvd (chemical adj vapor) sog "spin-on glass" "spin on glass" (sp?non adj glass) polysilazane)	US-PGPUB; USPAT	OR	ON	2005/07/14 17:00